

21. (Three Times Amended) A lithographic projection apparatus, comprising:
an illumination system constructed and arranged to supply a projection beam of radiation;
a first object table provided with a first object holder constructed and arranged to hold a mask;
a second object table provided with a second object holder constructed and arranged to hold a substrate;
a projection system constructed and arranged to utilize said radiation to image an irradiated portion of the mask onto a target portion of the substrate; and
at least one of said illumination system and projection system having a sensor with a surface on which radiation is incident and a capping layer covering said surface, said capping layer being formed of a relatively inert material,
wherein said relatively inert material is selected from the group consisting of: diamond-like carbon (C), Ru, Rh, Au, MgF₂, LiF, C₂F₄, TiN and compounds and alloys thereof.
22. (Amended) The lithographic projection apparatus according to claim 21,
wherein said relatively inert material is more inert than material from which remaining portions of said sensor are formed.
23. (Amended) The lithographic projection apparatus according to claim 21,
wherein said relatively inert material is less easily oxidized than the material from which remaining portions of said sensor are formed.
24. (Amended) The lithographic projection apparatus according to claim 21,
wherein said relatively inert material is harder than material from which remaining portions of said sensor is formed.
25. (Amended) The lithographic projection apparatus according to claim 21,
wherein said capping layer has a thickness in the range of from 0.5 nm to 10 nm.
28. (Amended) The lithographic projection apparatus according to claim 21,
wherein said capping layer comprises two sub-layers of different materials.

29. (Amended) The lithographic projection apparatus according to claim 21,
wherein said projection beam comprises radiation having a wavelength in the range of
from 8 nm to 20 nm.

See the attached Appendix for the changes made to effect the above-amended claims.